

Session #19: Homework Solutions

Problem #1

Calculate the vacancy fraction in copper (Cu) at (a) 20°C and (b) the melting point, 1085°C. Measurements have determined the values of the enthalpy of vacancy formation, ΔH_V , to be 1.03 eV and the entropic prefactor, A, to be 1.1.

Solution

number of sites / unit volume (also known as site density) is given by:

$$\frac{N_A}{V_{\text{molar}}} \therefore \text{site density} = 6.02 \times 10^{23} / 7.11 \text{ cm}^3 = 8.47 \times 10^{22}$$

→ vacancy density = f_v x site density

$$(a) f_v = A e^{-\frac{\Delta H_V}{k_B T}} = 1.1 \times e^{-\frac{1.03 \times 1.6 \times 10^{-19}}{1.38 \times 10^{-22} \times (20 + 273)}} = 2.19 \times 10^{-18}$$

$$\text{vacancy density at } 20^\circ\text{C} = 1.85 \times 10^5 \text{ cm}^{-3}$$

$$(b) f_v = A e^{-\frac{\Delta H_V}{k_B T}} = 1.1 \times e^{-\frac{1.03 \times 1.6 \times 10^{-19}}{1.38 \times 10^{-22} \times (20 + 1085)}} = 1.67 \times 10^{-4}$$

$$\text{vacancy density at } 1085^\circ\text{C} = 1.41 \times 10^{19} \text{ cm}^{-3}$$

Note that the ratio of $f_v(1085^\circ\text{C}) / f_v(20^\circ\text{C}) = 7.62 \times 10^{13}$!

Problem #2

In iridium (Ir), the vacancy fraction, n_v/N , is 3.091×10^{-5} at 1234°C and 5.26×10^{-3} at the melting point. Calculate the enthalpy of vacancy formation, ΔH_V .

Solution

All we need to know is the temperature dependence of the vacancy density:

$$\frac{n_v}{N} = A e^{-\frac{\Delta H_V}{RT}}, \text{ where } T \text{ is in Kelvins and the melting point of Ir is } 2446^\circ\text{C}$$

$$3.091 \times 10^{-5} = A e^{-\frac{\Delta H_V}{RT_1}}, \text{ where } T_1 = 1234^\circ\text{C} = 1507 \text{ K}$$

$$5.26 \times 10^{-3} = A e^{-\frac{\Delta H_V}{RT_2}}, \text{ where } T_2 = 2446^\circ\text{C} = 2719 \text{ K}$$

Taking the ratio:

$$\frac{5.26 \times 10^{-3}}{3.091 \times 10^{-5}} = \frac{Ae^{-\frac{\Delta H_V}{RT_1}}}{Ae^{-\frac{\Delta H_V}{RT_2}}} = e^{-\frac{\Delta H_V}{R} \left(\frac{1}{T_1} - \frac{1}{T_2} \right)}$$

$$\therefore \ln 170.2 = -\frac{\Delta H_V}{R} \left(\frac{1}{T_1} - \frac{1}{T_2} \right)$$

$$\therefore \Delta H_V = -\frac{R \times \ln 170.2}{\frac{1}{1507} - \frac{1}{2719}} = -\frac{8.314 \times \ln 170.2}{\frac{1}{1507} - \frac{1}{2719}} = 1.44 \times 10^5 \text{ J/mole} \cdot \text{vac}$$

$$\therefore \Delta H_V = \frac{1.44 \times 10^5}{6.02 \times 10^{23}} = 2.40 \times 10^{-19} \text{ J/vac} = 1.5 \text{ eV/vac}$$

Problem #3

A formation energy of 2.0 eV is required to create a vacancy in a particular metal. At 800°C there is one vacancy for every 10,000 atoms.

- (a) At what temperature will there be one vacancy for every 1,000 atoms?
- (b) Repeat the calculation, but this time with an activation energy of 1.0 eV. Note the big change in the temperature interval necessary to obtain the same change in vacancy concentration as was the case with an activation energy of 2.0 eV.

Solution

(a) We need to know the temperature dependence of the vacancy density:

$$\frac{1}{10^4} = Ae^{-\frac{\Delta H_V}{kT_1}} \quad \text{and} \quad \frac{1}{10^3} = Ae^{-\frac{\Delta H_V}{kT_x}}$$

$$\text{From the ratio: } \frac{\frac{1}{10^4}}{\frac{1}{10^3}} = \frac{10^3}{10^4} = \frac{Ae^{-\frac{\Delta H_V}{kT_1}}}{Ae^{-\frac{\Delta H_V}{kT_x}}} \quad \text{we get } -\ln 10 = -\frac{\Delta H_V}{k} \left(\frac{1}{T_1} - \frac{1}{T_x} \right)$$

$$\therefore \left(\frac{1}{T_1} - \frac{1}{T_x} \right) = \frac{k \ln 10}{\Delta H_V}$$

$$\frac{1}{T_x} = \frac{1}{T_1} - \frac{k \ln 10}{\Delta H_V} = \frac{1}{1073} - \frac{1.38 \times 10^{-23} \times \ln 10}{2 \times 1.6 \times 10^{-19}} = 8.33 \times 10^{-4}$$

$$T_x = 1200 \text{ K} = 928^\circ\text{C}$$

- (b) Repeat the calculation following the method given above but with $\Delta H_v = 1.0 \text{ eV}$ to find that $T_x = 1364 \text{ K} = 1091^\circ\text{C}$

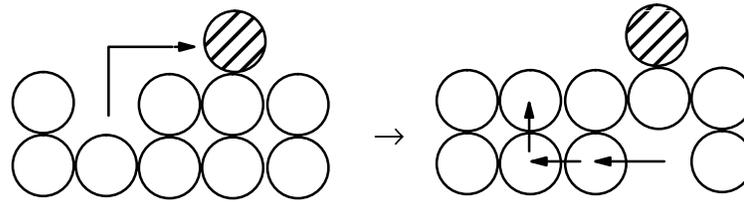
Note: the change in ΔH_v from 2.0 eV to 1.0 eV resulted in a change from 128 K to 291 K in ΔT .

Problem #4

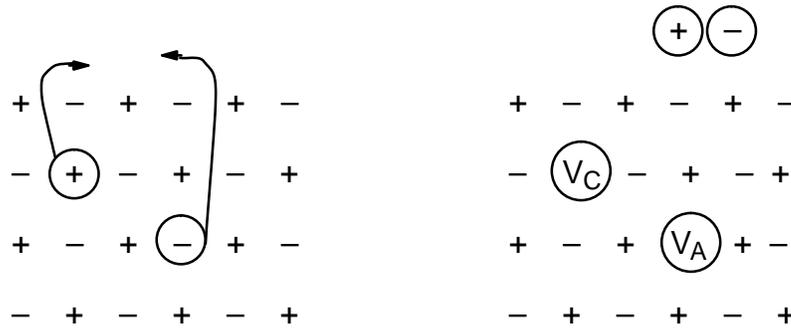
On appropriate schematic drawings show the generation and characteristics of Schottky defects in (a) a closed-packed metal, (b) an ionic crystal and (c) a semiconductor.

Solution

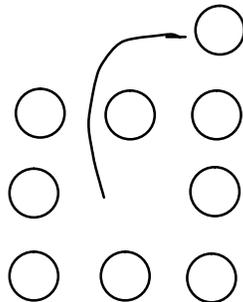
(a)



(b)



(c)



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